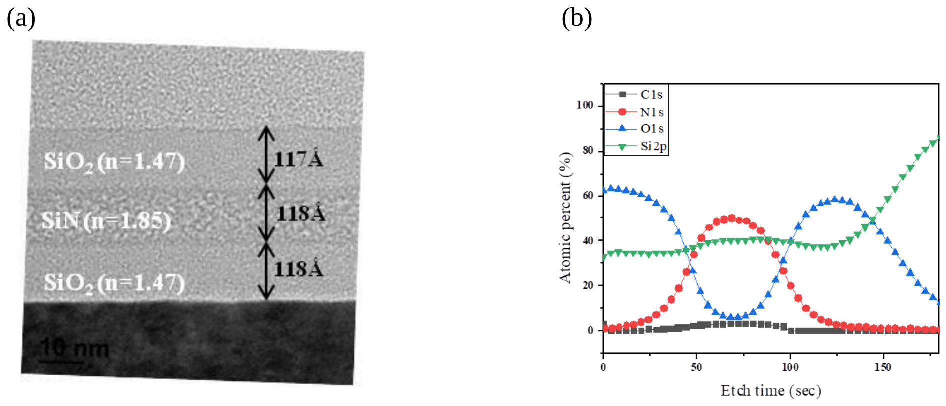

Fig 1. The deposited laminate was stacked the $SiO_2/SiN_x/SiO_2$ film in order. The laminate film was analyzed by (a) TEM, ellipsometer, (b) XPS depth profile. WVTR of the multilayer film was measured using a MOCON Aquatran 2 for 100 hours.

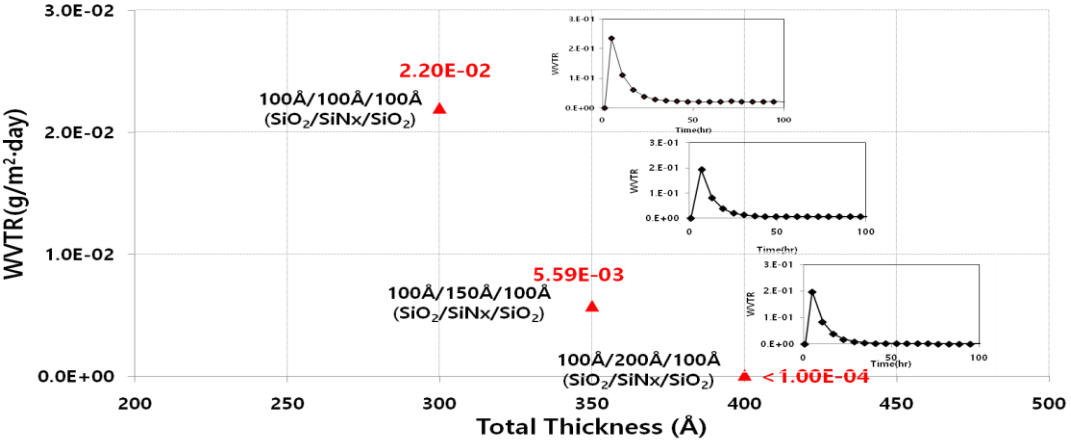

Fig 2. The WVTR characteristics according to the SiNx thickness in the SiO2 / SiNx / SiO2 laminated structure are shown. WVTR of the deposited laminate thin film(SiO2/SiNx/SiO2) be Measured for 100 hours using Aquatran 2 from MOCON.

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